# Microelectronics Circuit Analysis and Design

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Chapter 1

Semiconductor Materials and Devices

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### In this chapter, we will:

- Gain a basic understanding of semiconductor material properties
  - > Two types of charged carriers that exist in a semiconductor
  - > Two mechanisms that generate currents in a semiconductor
- □ Determine the properties of a pn junction
  - ➤ Ideal current-voltage characteristics of a pn junction diode
- Examine dc analysis techniques for diode circuits using various models to describe the nonlinear diode characteristics
- Develop an equivalent circuit for a diode that is used when a small, time-varying signal is applied to a diode circuit

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## **Intrinsic Semiconductors**

- ☐ Ideally 100% pure material
  - ➤ Elemental semiconductors
    - Silicon (Si)
      - Most common semiconductor used today
    - Germanium (Ge)
      - First semiconductor used in p-n diodes
  - ➤ Compound semiconductors
    - Gallium Arsenide (GaAs)

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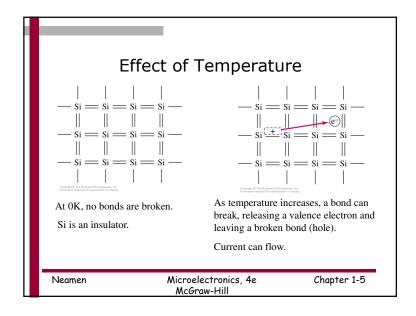
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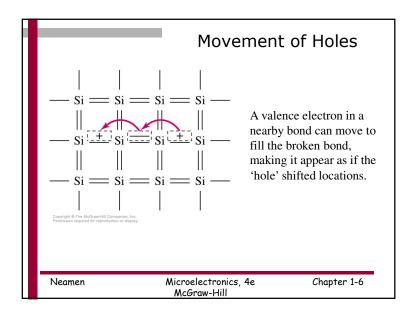
Covalent bonding of one Si atom with four other Si atoms to form tetrahedral unit cell.

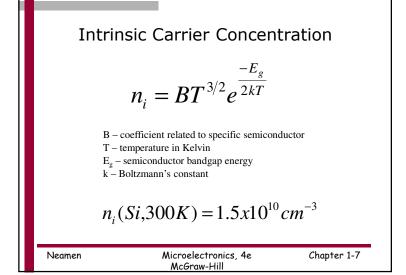
Valence electrons available at edge of crystal to bond to additional Si atoms.

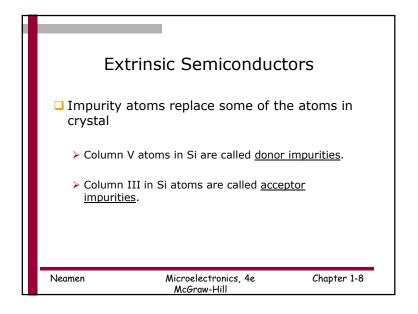
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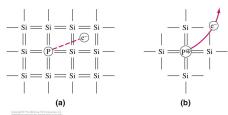








# Phosphorous - Donor Impurity in Si

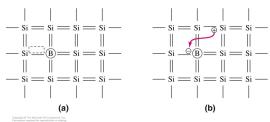


Phosphorous (P) replaces a Si atom and forms four covalent bonds with other Si atoms.

The <u>fifth</u> outer shell electron of P is easily freed to become a conduction band electron, adding to the number of electrons available to conduct current.

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# Boron – Acceptor Impurity in Si



Boron (B) replaces a Si atom and forms only **three** covalent bonds with other Si atoms.

The missing covalent bond is a hole, which can begin to move through the crystal when a valence electron from another Si atom is taken to form the fourth B-Si bond.

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# **Electron and Hole Concentrations**

ni = intrinsic carrier concentration (geo. Mean)

n = electron concentration

p = hole concentration

 $n_i^2 = n \cdot p$ 

n-type:

 $n = N_D$ , the donor concentration

 $p = n_i^2 / N_D$ 

p-type:

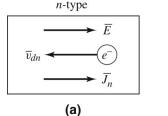
 $p = N_A$ , the acceptor concentration

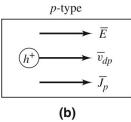
 $n = n_i^2 / N_A$ 

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## **Drift Currents**

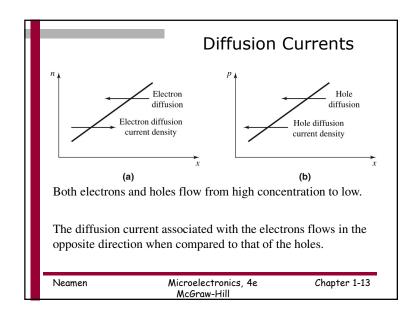


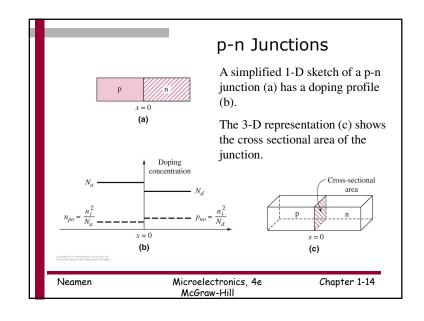


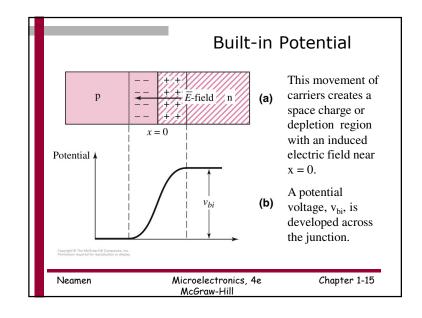
Electrons and hole flow in opposite directions when under the <u>influence of an electric field</u> at different velocities.

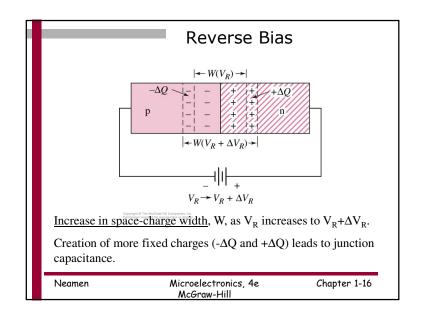
The drift currents associated with the electrons and holes are in the same direction.

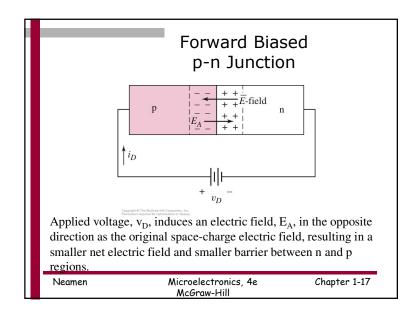
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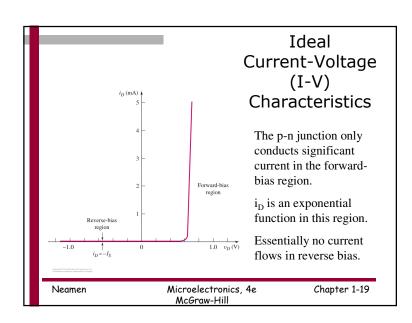


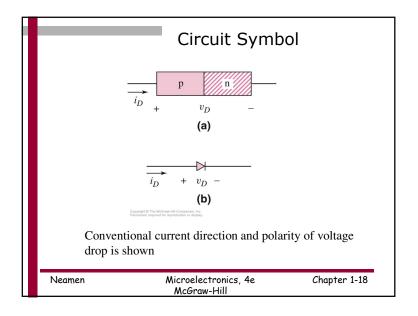












# Ideal Diode Equation

A fit to the I-V characteristics of a diode yields the following equation, known as the ideal diode equation:

$$I_D = I_s(e^{\frac{qv_D}{nkT}} - 1)$$

kT/q is also known as the thermal voltage,  $V_T$ .

 $V_T = 25.9 \text{ mV}$  when T = 300 K, room temperature.

$$I_D = I_s(e^{\frac{v_D}{V_T}} - 1)$$

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